

10528548_CLS1.txt
Most Frequently Occurring Classifications of Patents Returned
From A Search of 10528548 on June 06, 2006

Original Classifications

3 430/296
3 430/5
3 430/619
2 378/34
2 430/215
2 430/270.1
2 430/363
2 430/505

Cross-Reference Classifications

4 430/269
4 430/311
3 250/492.1
3 250/492.2
3 430/323
3 430/531
3 430/604
3 430/967
2 250/492.3
2 257/E21.032
2 257/E21.242
2 257/E21.346
2 257/E21.407
2 257/E21.454
2 430/203
2 430/236
2 430/296
2 430/320
2 430/321
2 430/325
2 430/326
2 430/5
2 430/505
2 430/535
2 430/536
2 430/617
2 430/945
2 430/955
2 430/957
2 430/961
2 435/320.1
2 435/325

Combined Classifications

5 430/269
5 430/296
5 430/5
4 250/492.2
4 430/311
4 430/505
3 250/492.1
3 250/492.3
3 430/203
3 430/215
3 430/270.1
3 430/323
3 430/363
3 430/531

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2 378/34
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2 430/326
2 430/533
2 430/535
2 430/536
2 430/617
2 430/945
2 430/955
2 430/957
2 430/961
2 435/320.1
2 435/325
2 438/571

Titles of Most Frequently Occurring Classifications of Patents Returned
From A Search of 10528548 on June 06, 2006

- 5 430/269 (1 OR, 4 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
- 5 430/296 (3 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/296 .Electron beam imaging
- 5 430/5 (3 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/4 RADIATION MODIFYING PRODUCT OR PROCESS OF
MAKING
430/5 .Radiation mask
- 4 250/492.2 (1 OR, 3 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices
- 4 430/311 (0 OR, 4 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/311 .Making electrical device
- 4 430/505 (2 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/495.1 RADIATION SENSITIVE PRODUCT
430/502 .Two or more radiation-sensitive layers
containing other than that characterized by the
composition
of a single sensitive layer
430/503 ..Layers sensitive to different spectral
regions
430/505 ...Developing inhibitor or processing
ingredient containing
- 3 250/492.1 (0 OR, 3 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
- 3 250/492.3 (1 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.3 .Ion or electron beam irradiation
- 3 430/203 (1 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,

430/199 COMPOSITION, OR PRODUCT THEREOF
TRANSFER PROCEDURE BETWEEN IMAGE AND IMAGE
LAYER, IMAGE RECEIVING LAYERS, OR ELEMENT CONTAINING AN
IMAGE RECEIVING LAYER OR AN INGREDIENT FOR FORMING AN
IMAGE RECEIVING LAYER

430/202 .Diffusion transfer process, element, or
identified image receiving layers therefor

430/203 ..By uniform application of heat, element, or
image receiving layer therefor

3 430/215 (2 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/199 TRANSFER PROCEDURE BETWEEN IMAGE AND IMAGE
LAYER, IMAGE RECEIVING LAYERS, OR ELEMENT CONTAINING
AN IMAGE RECEIVING LAYER OR AN INGREDIENT FOR FORMING AN
IMAGE RECEIVING LAYER

430/202 .Diffusion transfer process, element, or
identified image receiving layers therefor

430/211 ..Element or identified image receiving layers
for dye image formation

430/212 ...Element containing silver salt sensitizer or
either element or image receiving layer for use
therewith

430/215Identified synthetic polymeric binder
contained in nonradiation sensitive processing
composition permeable layer other than an image receiving or
neutralizing layer

3 430/270.1 (2 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT

430/270.1 .Radiation sensitive composition or product or
process of making

3 430/323 (0 OR, 3 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT

430/322 .Forming nonplanar surface

430/323 ..Including etching substrate

3 430/363 (2 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/357 COLOR IMAGING PROCESS

430/363 .Laser or radiation exposure other than visible
light

3 430/531 (0 OR, 3 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/495.1 RADIATION SENSITIVE PRODUCT

430/523 .Identified backing or protective layer
containing
430/531 ..Synthetic resin or cellulose derivative
containing

3 430/604 (0 OR, 3 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/495.1 RADIATION SENSITIVE PRODUCT
430/564 .Silver compound sensitizer containing
430/599 ..Hypersensitizing or latensifying ingredient
containing
430/604 ...Heavy metal or compound thereof

3 430/619 (3 OR, 0 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/495.1 RADIATION SENSITIVE PRODUCT
430/564 .Silver compound sensitizer containing
430/617 ..Silver compound other than halide, per se, or
composition for thermographic process process
430/618 ...Organic silver compound containing
430/619And inorganic silver compound

3 430/967 (0 OR, 3 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/966 X-RAY
430/967 .X-ray exposure process

2 250/491.1 (1 OR, 1 XR)
Class 250 : RADIANT ENERGY
250/491.1 MEANS TO ALIGN OR POSITION AN OBJECT RELATIVE
TO A SOURCE OR DETECTOR

2 257/E21.032 (0 OR, 2 XR)
Class 257 : ACTIVE SOLID-STATE DEVICES
257/E21.001 PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE
OR TREATMENT OF SEMICONDUCTOR OR SOLID-STATE DEVICES

OR OF

PARTS THEREOF (EPO)
257/E21.002 .Manufacture or treatment of semiconductor
device (EPO)
257/E21.023 ..Making mask on semiconductor body for
further photolithographic processing (EPO)
257/E21.024 ...Comprising organic layer (EPO)
257/E21.026Characterized by treatment of photoresist
layer (EPO)
257/E21.032Ion lithographic process (EPO)

2 257/E21.242 (0 OR, 2 XR)
Class 257 : ACTIVE SOLID-STATE DEVICES
257/E21.001 PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE
OR TREATMENT OF SEMICONDUCTOR OR SOLID-STATE

DEVICES OR OF

PARTS THEREOF (EPO)
257/E21.002 .Manufacture or treatment of semiconductor
device (EPO)
257/E21.04 ..Device having at least one potential-jump
barrier or surface barrier, e.g., PN junction,
depletion layer, carrier concentration layer (EPO)
257/E21.085 ...Device having semiconductor body comprising

without
 257/E21.211Treatment of semiconductor body using
 material on process other than deposition of semiconductor
 material, or a substrate, diffusion or alloying of impurity
 257/E21.214To change their surface-physical
 cutting characteristics or shape, e.g., etching, polishing,
 (EPO)
 257/E21.24To form insulating layer thereon, e.g.,
 (EPO) for masking or by using photolithographic technique
 257/E21.241Post-treatment (EPO)
 257/E21.242Of organic layer (EPO)

2 257/E21.346 (0 OR, 2 XR)
 Class 257 : ACTIVE SOLID-STATE DEVICES
 257/E21.001 PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE
 OR TREATMENT OF SEMICONDUCTOR OR SOLID-STATE
 DEVICES OR OF PARTS THEREOF (EPO)
 257/E21.002 .Manufacture or treatment of semiconductor
 device (EPO)
 257/E21.04 ..Device having at least one potential-jump
 depletion barrier or surface barrier, e.g., PN junction,
 layer, carrier concentration layer (EPO)
 257/E21.085 ...Device having semiconductor body comprising
 without Group IV elements or Group III-V compounds with or
 impurities, e.g., doping materials (EPO)
 257/E21.328Radiation treatment (EPO)
 257/E21.331With high-energy radiation (EPO)
 257/E21.334Producing ions for implantation (EPO)
 257/E21.346Using mask (EPO)

2 257/E21.407 (0 OR, 2 XR)
 Class 257 : ACTIVE SOLID-STATE DEVICES
 257/E21.001 PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE
 OR TREATMENT OF SEMICONDUCTOR OR SOLID-STATE
 DEVICES OR OF PARTS THEREOF (EPO)
 257/E21.002 .Manufacture or treatment of semiconductor
 device (EPO)
 257/E21.04 ..Device having at least one potential-jump
 depletion barrier or surface barrier, e.g., PN junction,
 layer, carrier concentration layer (EPO)
 257/E21.085 ...Device having semiconductor body comprising
 without Group IV elements or Group III-V compounds with or
 impurities, e.g., doping materials (EPO)
 257/E21.394Multi-step process for the manufacture of
 unipolar device (EPO)
 257/E21.4Field-effect transistor (EPO)
 257/E21.405Active layer is Group III-V compound,
 e.g., III-V velocity modulation transistor (VMT), NERFET
 (EPO)

257/E21.407With an heterojunction interface channel
or gate, e.g., HFET, HIGFET, SI SFET, HJFET, HEMT (EPO)

2 257/E21.454 (0 OR, 2 XR)
Class 257 : ACTIVE SOLID-STATE DEVICES
257/E21.001 PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE
OR TREATMENT OF SEMICONDUCTOR OR SOLID-STATE
DEVICES OR OF
PARTS THEREOF (EPO)
257/E21.002 .Manufacture or treatment of semiconductor
device (EPO)
257/E21.04 ..Device having at least one potential-jump
barrier or surface barrier, e.g., PN junction,
depletion
layer, carrier concentration layer (EPO)
257/E21.085 ...Device having semiconductor body comprising
without Group IV elements or Group III-V compounds with or
impurities, e.g., doping materials (EPO)
257/E21.394Multi-step process for the manufacture of
unipolar device (EPO)
257/E21.4Field-effect transistor (EPO)
257/E21.45With Schottky gate, e.g., MESFET (EPO)
257/E21.451Active layer being Group III-V compound
(EPO)
257/E21.452Lateral single-gate transistors (EPO)
257/E21.454Process wherein final gate is made
before formation, e.g., activation anneal, of source and
drain regions in active layer (EPO)

2 378/34 (2 OR, 0 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/1 SPECIFIC APPLICATION
378/34 .Lithography

2 430/236 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/199 TRANSFER PROCEDURE BETWEEN IMAGE AND IMAGE
LAYER, IMAGE RECEIVING LAYERS, OR ELEMENT CONTAINING
AN
IMAGE RECEIVING LAYER OR AN INGREDIENT FOR FORMING AN
IMAGE
RECEIVING LAYER
430/202 .Diffusion transfer process, element, or
identified image receiving layers therefor
430/235 ..Dye image formation process
430/236 ...Using silver salt sensitizer

2 430/320 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/320 .Making named article

2 430/321 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF

RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT

430/320 .Making named article
430/321 ..Optical device

2 430/325 (0 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT

430/322 .Forming nonplanar surface
430/325 ..Post image treatment to produce elevated
pattern

2 430/326 (0 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR

OR

PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT

430/322 .Forming nonplanar surface
430/325 ..Post image treatment to produce elevated
pattern
430/326 ...Pattern elevated in radiation unexposed
areas

2 430/533 (1 OR, 1 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/495.1 RADIATION SENSITIVE PRODUCT
430/523 .Identified backing or protective layer
containing
430/531 ..Synthetic resin or cellulose derivative
containing
430/533 ...Polyester or polycarbonate

2 430/535 (0 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/495.1 RADIATION SENSITIVE PRODUCT
430/523 .Identified backing or protective layer
containing
430/531 ..Synthetic resin or cellulose derivative
containing
430/533 ...Polyester or polycarbonate
430/534Next to polymer of unsaturated monomer
430/535Polymer of unsaturated ester or halide

2 430/536 (0 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/495.1 RADIATION SENSITIVE PRODUCT
430/523 .Identified backing or protective layer
containing
430/531 ..Synthetic resin or cellulose derivative
containing
430/536 ...Polymer of unsaturated monomer

2 430/617 (0 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/495.1 RADIATION SENSITIVE PRODUCT
 430/564 .Silver compound sensitizer containing
 430/617 ..Silver compound other than halide, per se, or
 composition for thermographic process process

2 430/945 (0 OR, 2 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/945 LASER BEAM

2 430/955 (0 OR, 2 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/955 PRECURSOR COMPOUND

2 430/957 (0 OR, 2 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/955 PRECURSOR COMPOUND
 430/957 .Development inhibitor releaser (DIR)

2 430/961 (0 OR, 2 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/961 PROTECTIVE OR ANTIABRASION LAYER

2 435/320.1 (0 OR, 2 XR)
 Class 435 : CHEMISTRY: MOLECULAR BIOLOGY AND MICROBIOLOGY
 435/320.1 VECTOR, PER SE (E.G., PLASMID, HYBRID PLASMID,
 COSMID, VIRAL VECTOR, BACTERIOPHAGE VECTOR, ETC.)
 BACTERIOPHAGE VECTOR, ETC.)

2 435/325 (0 OR, 2 XR)
 Class 435 : CHEMISTRY: MOLECULAR BIOLOGY AND MICROBIOLOGY
 435/325 ANIMAL CELL, PER SE (E.G., CELL LINES, ETC.);
 COMPOSITION THEREOF; PROCESS OF PROPAGATING, MAINTAINING

OR

PRESERVING AN ANIMAL CELL OR COMPOSITION THEREOF; PROCESS
 OF ISOLATING OR SEPARATING AN ANIMAL CELL OR COMPOSITION
 THEREOF; PROCESS OF PREPARING A COMPOSITION CONTAINING AN
 ANIMAL CELL; CULTURE MEDIA THEREFORE

2 438/571 (1 OR, 1 XR)
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
 438/570 FORMING SCHOTTKY JUNCTION (I.E.,
 SEMICONDUCTOR-CONDUCTOR RECTIFYING JUNCTION CONTACT)
 438/571 .Combined with formation of ohmic contact to
 semiconductor region